

# EI-27003: Electronics Devices and Circuits

## Lecture - 10

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### **LECTURE - 10**

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# Derivation of Drain Current $I_D$

➤ Let us assume that  $V_{GS}$  is applied between Gate and Source with  $V_{GS} > V_t$  to induce channel.

➤ Also assume that  $V_{DS}$  is applied between drain and source.

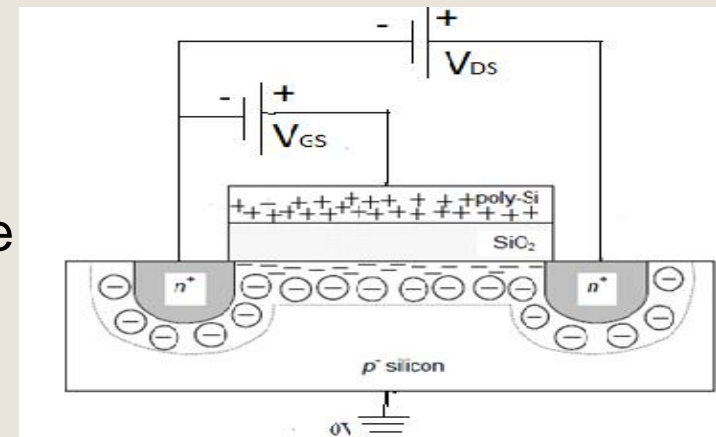
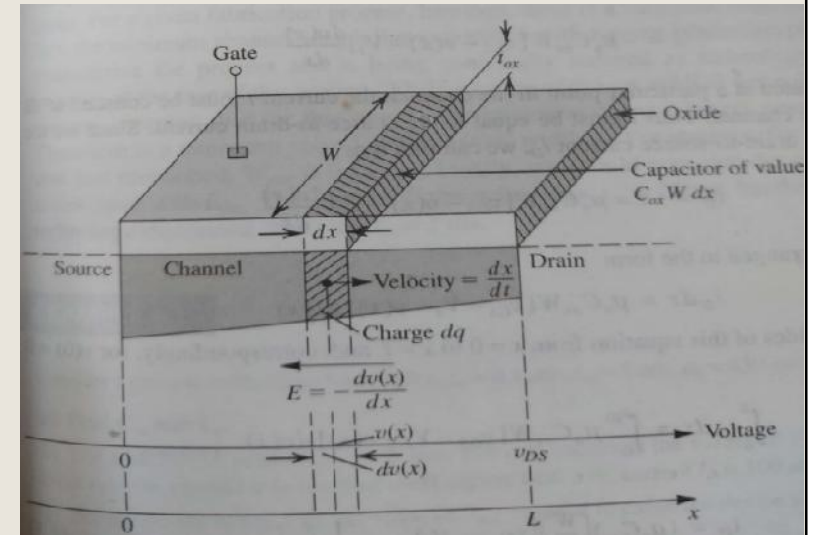
➤ Let us consider triode region in which  $V_{DS} < (V_{GS} - V_t)$

➤ In this case channel will have tapered shape as shown in cross sectional view.

➤ Now gate is connected to +ve plate of Battery have +ve charges on it.

➤ Channel formed is of electrons (-ve), have -ve charges on it.

➤ In between these +ve and -ve layers, there is  $\text{SiO}_2$  layer which is dielectric.



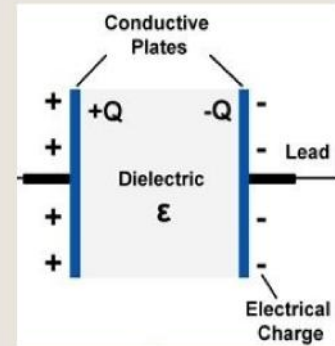
# Derivation.....

- Hence the gate and channel region forms a parallel plate capacitor. If capacitance per unit gate area is denoted as  $C_{ox}$  and thickness of oxide layer is  $t_{ox}$ , then

$$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}} \text{ ----- (1)}$$

- Where:  $\epsilon_{ox}$  is the permittivity of silicon dioxide

$$\epsilon_{ox} = 3.9 \times \epsilon_0 = 3.9 \times 8.8854 \times 10^{-12} = 3.45 \times 10^{-11} \text{ F/m}$$



- Now consider cross sectional view and consider infinitesimal strip of the gate at distance  $x$  from source.
- The capacitance of this strip is  $= C_{ox} \cdot w \cdot dx$  -----(2)
- To find the charge stored on this strip of gate capacitance, we multiply the capacitance by effective voltage between gate and channel at point  $x$ .
- This effective voltage at point  $x$  will be  $= [V_{GS} - V_t - V(x)]$  -----(3)
- Hence electron charge  $dq$  in infinitesimal portion of channel at point  $x$  is

$$dq = - C_{ox} \cdot w \cdot dx [V_{GS} - V_t - V(x)] \text{ -----(4)}$$

-ve sign is negative charge.

# Derivation.....

- The voltage  $V_{DS}$  produces electric field along the channel in the negative  $x$  direction. At point  $x$  this field can be expressed as;

$$E(x) = -\frac{dV(x)}{dx} \text{ -----(5)}$$

- The electric field  $E(x)$  causes the electron charge  $dq$  to drift towards the drain with velocity  $dx/dt$

$$\frac{dx}{dt} = -\mu_n E(x) = \mu_n \frac{dV(x)}{dx} \text{ -----(6)}$$

- Where  $\mu_n$  is the mobility of electrons in the channel.
- Thus the resulting drift current 'i' is obtained as:

$$i = \frac{dq}{dt} \text{ or } \frac{dq}{dx} \frac{dx}{dt} \text{ -----(7)}$$

- Substitute  $\frac{dq}{dx}$  from eq.(4) and  $\frac{dx}{dt}$  from eq.(6), then

$$i = -\mu_n C_{ox} \cdot w \cdot [V_{GS} - V_t - V(x)] \frac{dV(x)}{dx} \text{ -----(8)}$$

# Derivation.....

- Although evaluated at a particular point in the channel, the drift current (electron current) 'i' must be constant at all points along the channel.
- As we are interested in drain current (conventional current)  $I_D$ :

$$I_D = -i = \mu_n C_{ox} \cdot w \cdot [V_{GS} - V_t - V(x)] \frac{dV(x)}{dx} \text{ -----(9)}$$

- Rearrange this equation:

$$I_D dx = \mu_n C_{ox} \cdot w \cdot [V_{GS} - V_t - V(x)] dV(x) \text{ -----(10)}$$

- Integrating both sides of this equation from  $x=0$  to  $x=L$  correspondingly for  $V(0)=0$  to  $V(L)=V_{DS}$

$$\int_0^L I_D dx = \int_0^{V_{DS}} \mu_n C_{ox} \cdot w \cdot [V_{GS} - V_t - V(x)] dV(x) \text{ -----(11)}$$

Solving this integration gives:

$$I_D = \mu_n C_{ox} (W/L) [(V_{GS} - V_t) V_{DS} - \frac{1}{2} V_{DS}^2] \text{ for } V_{DS} < (V_{GS} - V_t) \text{ triode region} \text{ -----(12)}$$



# Drain Current $I_D$ for Saturation Region

- As we know if  $V_{DS}$  becomes equals to  $(V_{GS}-V_t)$ , the channel gets pinched-off and NMOS is just on verge of Saturation.
- So equation (12) becomes:

$$I_D = \mu_n C_{ox} (W/L) [(V_{GS}-V_t)V_{DS} - \frac{1}{2}V_{DS}^2] \text{-----(12)}$$

Substitute  $V_{DS} = (V_{GS}-V_t)$

$$I_D = \mu_n C_{ox} (W/L) [(V_{GS}-V_t)(V_{GS}-V_t) - \frac{1}{2}(V_{DS}-V_t)^2]$$

$$I_D = \frac{1}{2} \mu_n C_{ox} (W/L) (V_{DS}-V_t)^2 \quad \text{for } V_{DS} \geq (V_{GS}-V_t) \text{ Saturation Region}$$

- Here  $\mu_n C_{ox}$  is constant and is called as **Process Trans-conductance Parameter**.
- It is denoted by  $K_n$  and has dimensions of  $A/V^2$

$$I_D = K_n (W/L) [(V_{GS}-V_t)V_{DS} - \frac{1}{2}V_{DS}^2] \quad \text{Triode region}$$

$$I_D = \frac{1}{2} K_n (W/L) (V_{DS}-V_t)^2 \quad \text{Saturation region}$$

Its time for Quiz

<https://forms.gle/TWepKdJg1hMjJZNV6>